

ABSTRACT

Disclosed is a fume removal apparatus for a semiconductor manufacturing chamber. The disclosed fume removal apparatus
5 for a semiconductor manufacturing chamber comprises: a fume exhaust pipe; a fume exhaust pipe opening-and-closing valve; a vacuum pump; and a control member, wherein the control member opens the fume exhaust pipe by opening the fume exhaust pipe opening-and-closing valve and forms a vacuum inside the fume
10 exhaust pipe by operating the vacuum pump, so that fumes within the semiconductor manufacturing chamber can flow in along the fume exhaust pipe and be discharged to the outside. The disclosed fume removal apparatus for a semiconductor manufacturing chamber enables fumes to be rapidly, conveniently,
15 and reliably removed from the semiconductor manufacturing chamber, and thus has an advantage of enabling a worker who should approach the inside of the semiconductor manufacturing chamber to safely perform work without coming into contact with the fumes.